

PROCEEDINGS OF SPIE

***Optical Materials and Structures  
Technologies III***

**William A. Goodman  
Joseph L. Robichaud**  
*Editors*

**26–27 August 2007  
San Diego, California, USA**

*Sponsored and Published by  
SPIE*

**Volume 6666**

Proceedings of SPIE, 0277-786X, v. 6666

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Please use the following format to cite material from this book:

Author(s), "Title of Paper," in *Optical Materials and Structures Technologies III*, edited by William A. Goodman, Joseph L. Robichaud, Proceedings of SPIE Vol. 6666 (SPIE, Bellingham, WA, 2007) Article CID Number.

ISSN 0277-786X  
ISBN 9780819468147

Published by

**SPIE**

P.O. Box 10, Bellingham, Washington 98227-0010 USA  
Telephone +1 360 676 3290 (Pacific Time) · Fax +1 360 647 1445  
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